

EFFICIENT CLEANING BY SECONDARY IN-SITU ACTIVATION
OF ETCH PRECURSOR FROM REMOTE PLASMA SOURCE

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ABSTRACT

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An electro-negative cleaning or etchant gas, such as fluorine, that was ionized from a stable supply gas such as NH_3 in a secondary chamber and recombined in the primary chamber, is re-ionized within the primary chamber by electron attachment by ionizing an electron donor gas, such as helium, in the primary chamber.